

Design and fabrication of double gradient multilayers for a Kirkpatrick-Baez focusing system

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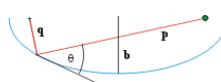
Double gradient multilayer

Idea: Figured optics for broad energy bands

- Incident angle variation followed by lateral gradient
- Energy band defined by depth-gradient
- Fixed-exit focusing device for variable energies ("micro-spectroscopy")

Example: Elliptic mirror with $[Ru/B_4C]_{35}$ multilayer coating to be used at energy range 6000-13000 eV with $\Delta E/E \approx 16\%$

$$\text{Lateral gradient } \Lambda = \frac{\lambda \cdot m}{2\sqrt{n^2 - \cos^2 \theta}} \quad \sin \theta = \frac{b}{\sqrt{pq}}$$



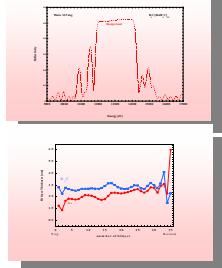
Depth-graded multilayers

Goal

- Design multilayer with particular reflectivity profile
- $R = R(\theta)$ for $E = \text{const.}$
- $R = R(E)$ for $\theta = \text{const.}$
- Find vertical composition profile : 71 independent layers

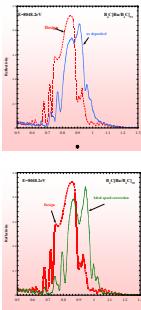
Design method

- Choose appropriate starting solution
- Apply fit algorithm to optimize the structure



Experimental aspects

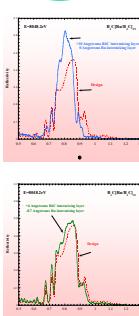
Regular compensation



Thickness control

- Depth: variation of exposure time / total speed by analytical function or look-up table
- Lateral: modification of speed profile
- Both depth and lateral gradient possible

Interdiffusion compensation added



Tests and calibrations

- At $E=8.048.2$ keV (Lab reflectometer energy)

Required corrections

- Real film densities
- Layer interdiffusion → variable growth rate
- Machine drift → linear compensation

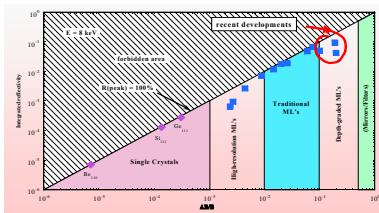
Summary and perspectives

Advantages

- Focusing ML over a broad angle range
- Combination of lateral and depth gradient
- Focusing at fixed distance and variable energies

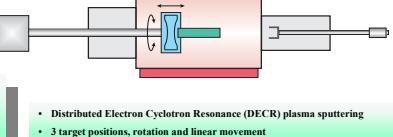
Future perspectives

- Integration into beamline optics
- Global optimization algorithm for both gradients



Deposition system

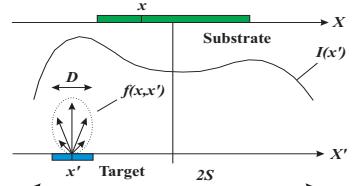
- Ar pressure 1.3×10^{-3} mbar
- Polarization voltage $U = 500...2000$ V (DC/RF)
- Particle flux $R = 0.02...0.10$ nm/s
- Deposition temperature $T_{\text{dep}} = 100^\circ\text{C}$



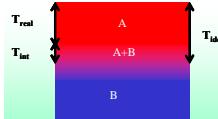
Thickness control

Basic model assumptions

- Total particle flux \propto weighted sum of Gaussian (G) + Lorentzian (L)
- Rate $R \propto$ ion current I at $U=\text{const}$
- Local velocity $v \Rightarrow$ local "exposure time" $dt = dx/v$
- Integration over total stroke $2S$ of target movement



Interdiffusion thickness determination

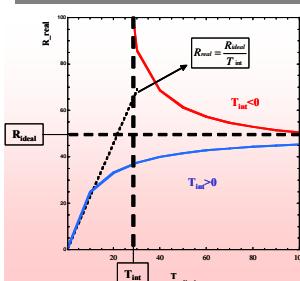


Thickness definition:

$$T_{\text{ideal}} = T_{\text{real}} + T_{\text{int}}$$

Sputtering rates definition:

$$R_{\text{real}} = R_{\text{ideal}} * \frac{T_{\text{real}}}{T_{\text{real}} + T_{\text{int}}}$$



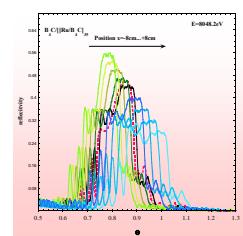
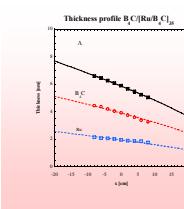
Periodic multilayer

- Ideal speed determination
- Interdiffusion layer for each material

Non periodic multilayer

- Shift on angle → interdiffusion of B4C
- Broad peak → interdiffusion of B4C

Lateral gradient - Results



Double graded multilayers - Energy Dispersion

$$\text{Bragg equation: } E = \frac{h \cdot c}{2 \cdot \Lambda \cdot \sqrt{n^2 - \cos^2 \theta}}$$

$$\text{Elliptical mirror: } \sin \theta = \frac{b}{\sqrt{pq}}$$

$$E = \frac{h \cdot c}{2 \cdot \Lambda \cdot \sqrt{n^2 - 1 + \frac{b^2}{pq}}}$$

→ Dispersion "along ML mirror"

